From:
 Jeromin, Lori - 0666 - MITLL

 To:
 Campbell, Joseph - 0552 - MITLL

**Subject:** Re: IEEE Milestone Award for the "Development of 193-nm Projection Photolithography"

**Date:** Wednesday, April 27, 2022 12:42:30 PM

Joe -

Advances in photolithography have certainly helped enable additional technical development! The Boston Section of Life Members supports an IEEE Milestone for the Development of 193-nm Projection Photolithography.

Lori (Jeromin, Chair, IEEE Boston Section Life Members)

p.s. No additional input from other LMs to add at the moment, but I'll send on as an addendum when/if interesting input come in.

From: "Campbell, Joseph - 0552 - MITLL" <jpc@ll.mit.edu>

Date: Thursday, April 21, 2022 at 10:40 PM

To: Lori Jeromin <lorilee@ll.mit.edu>

Subject: IEEE Milestone Award for the "Development of 193-nm Projection Photolithography"

Dear Lori Jeromin,

We would be grateful to receive the *IEEE Boston Section Affinity Group for Life Members'* endorsement of the IEEE Milestone Award proposal on the <u>Development of 193-nm Projection Photolithography</u>:

MIT Lincoln Laboratory pioneered R&D, engineering, testing, and demonstration of 193-nm projection lithography, the semiconductor manufacturing technology that has since become mainstream worldwide. During 1984–1996, Lincoln Laboratory became an international center of excellence, which, in collaboration with industrial partners and consortia, helped guide early-stage semiconductor manufacturing with 193 nm and paved the way to widespread adoption of this technology.

If you agree, could you please reply with an endorsement of MIT Lincoln Laboratory's IEEE Milestone Award proposal on the <u>Development of 193-nm Projection Photolithography</u>?

Kind regards,

Joe

## Joseph P. Campbell, PhD, FIEEE

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